



THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. Of: ANDRE et al.

Serial No.: 09/830,380

Filed: April 25, 2001

For: THIN LAYER OF HAFNIUM OXIDE AND DEPOSIT PROCESS

Group: 1774

Examiner: T. Dicus DOCKET: BREV 13186

Assistant Commissioner of Patents and Trademarks
Washington, D.C. 20231

AMENDMENT B

Dear Sir:

This amendment is being filed in response to the Official Action mailed October 4, 2002.

Please amend the application as follows:

IN THE SPECIFICATION:

Please replace the sub-paragraph beginning on page 14, line 15, with the following
rewritten paragraph:

A1
-- - Figure 3 between a layer of hafnium oxide comprising crystals of hafnium oxide
resulting from ion bombardment of the substrate and an amorphous layer according to the
invention.--

Please replace the sub-paragraph beginning on page 14, line 23, with the following
rewritten paragraph:

A2
-- - Figure 5 is a curve representing the reflection of a mirror component of Figure 4 in
function of wavelength.--

Please replace the paragraph beginning on page 15, line 15, with the following rewritten
paragraph:

HAYES SOLOWAY P.C.
130 W. CUSHING ST.
TUCSON, AZ 85701
TEL. 520.882.7623
FAX. 520.882.7643

175 CANAL STREET
MANCHESTER, NH 03101
TEL. 603.668.1400
FAX. 603.668.8567